

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Verhaverbeke

Serial No.: 10/676,182

Confirmation No.: Unknown

Filed:

September 30, 2003

For:

Dilute Sulfuric Peroxide at

Point-of-Use

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Examiner:

Group Art Unit: Unknown

Unknown

MAIL STOP DD Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

CERTIFICATE OF MAILING 37 CFR 1.8

I hereby certify that this correspondence is being deposited on December 2, 2003 with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450.

| <u>| /2/ (3/) - // (3</u> | Date

Signature /

INFORMATION DISCLOSURE STATEMENT

The Applicants, and the Attorney who signs below on the basis of the information supplied by the inventor and the information in his file, submit herewith patents, publications, or other information of which they are aware, which may be material to the examination of this application and in respect of which there may be a duty to disclose in accordance with 37 CFR § 1.56.

While the information submitted in this Information Disclosure Statement may be material pursuant to 37 CFR § 1.56, it is not intended to constitute an admission that any patent, publication, or other information referred to therein is prior art for this invention unless specifically designated as such.

In accordance with 37 CFR § 1.97, this Information Disclosure Statement is not to be construed as a representation that a search has been made or that no other possibly material information as defined under 37 CFR § 1.56(a) exists.

The patents and/or publications submitted herewith are set forth on the attached Form PTO-1449.

If the sum of \$180.00 is due under 37 CFR § 1.17(p) pursuant to § 1.97, the Commissioner is hereby authorized to charge this fee, and any other fee necessary to make this submission timely, to the Deposit Account No. 20-0782/APPM/8284/BTP.

Respectfully submitted,

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U.S. Department of Commerce Pater and Trademark Office Docket No.										Serial No.	
(PTO Form 1449 modified) JAN 0 2 2004 LIST OF PATENTS AND PUBLICATIONS CITED BY APPLICANT Appl								AMAT/8284/CMP/W- C/RKK		10/676,182	
								Applicant Verhaverbeke		Confirmation No.: Unknown	
(Use several sheets if necessary) Filing Date									Group		
Examiner Unknown								September 30, 2003		Unknown	
U.S. Paten	t Docu	ments					•				
*Examiner Initial		1		Issue Date		pplicant(s) ame	Class	Subclass	Filing Da Appropria		
	A1	5,326,490 0		7/05/94		lori, et al.	252	79.2	11/15/91	1	
	A2	5,294,570 0		3/15/94		leming, Jr., et al.	437	239	01/29/92	2	
	А3	5,052,421 10		0/01/91		lcMillen	134	2	07/27/90)	
	A4	4,220,706 09		9/02/80		pak	430	318	05/10/78	3	
	A5										
	A6										
	A7										
	A8										
	A9										
Foreign Pa	atent D	ocuments									
*Examiner Initial		Document Number		Date		Country	Class	Subclass	Trans	lation NO	
	B1	02/10480		02/07/02		wo	C23G	1/00			
	B2	01/24244		04/05/01		wo	H01L	21/311			
	B3	0 918 081 A1		05/26/99		EP	C09K	13/08			
	B4	0 477 504 A1		04/01/92		EP	H01L	21/306			
	B5	7183287		07/21/95		JP	H01L	21/308			
OTHER AF	RT.	<u> </u>				<u> </u>		<u>- </u>	· · · · · · · · · · · · · · · · · · ·		
*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.									
	C1	Archer, et al. "Real Fab Comparisons Reveal Advantage to Inorganic-based Polymer Removal," Solid State Technology – Semiconductor Manufacturing and Wafer Fabrication, December 2002									
	C2	Archer, et al. "Removing Postash Polymer Residue from BEOL Structures Using Inorganic Chemicals," Micro, June 2001									
	C3 Verhaverbeke, et al., Improved Rinsing Efficiency After SPM (H ₂ SO ₄ /H ₂ O ₂) by Adding Proceedings of the Second International Symposium on Ultra-Clean Processing of Si Surfaces (1994)										
	C4	Khan, "Use of Lithographically Defined Metal Masks in Selective Chemical Etc. Patterns in Thin Films: Microelectronic Applications," Thin Solid Films, 206 (19									
Examiner	xaminer							Date Considered			
						ner or not citation is sidered. Include co					